

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : Box: **Patent Applications**

Jun HATAKEYAMA et al. :

Serial No.: Not Yet Assigned :

Filed: April 26, 2001 :

For: **POLYMER, CHEMICALLY AMPLIFIED RESIST COMPOSITION AND PATTERNING PROCESS**

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to calculating the filing fee and examination of the above-identified application, please amend this application, as follows:

IN THE CLAIMS:

Please amend claims 3 and 4 as follows:

3. (Amended) A chemically amplified resist composition comprising the polymer of claim 1.

4. (Amended) A chemically amplified positive resist composition comprising
- (A) the polymer of claim 1,
 - (B) an organic solvent, and
 - (C) a photoacid generator.

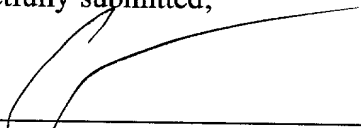
09244-04260

REMARKS

The purpose of this preliminary amendment is to eliminate the multiple dependency of the claims in order to avoid the additional fee.

Attached hereto is a marked-up version of the changes made to claims 3 and 4 by the current amendment. The attached page is captioned "Version with markings to show changes made."

Respectfully submitted,



Anthony J. Zelano (27,969)

Attorney for Applicants

MILLEN, WHITE, ZELANO & BRANIGAN, P. C.

2200 Clarendon Boulevard, Suite 1400

Arlington, Virginia 22201

(703) 243-6333

Filed: April 25, 2001

AJZ/tal:K:\PAT\kojim\393\pre amend.wpd

094214-042601
T09240-4T24860

VERSION WITH MARKINGS TO SHOW CHANGES MADE

Claims 3 and 4 have been amended as follows:

3. (Amended) A chemically amplified resist composition comprising the polymer of claim 1 ~~or~~ 2.
4. (Amended) A chemically amplified positive resist composition comprising
- (A) the polymer of claim 1 ~~or~~ 2,
 - (B) an organic solvent, and
 - (C) a photoacid generator.